L Number	Hits	Search Text	DB	Time stamp
1	2	jp-2002116544-\$.did.	USPAT;	2003/06/02 07:50
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	l
-	752	NAKANO-T NAKANO-TATSUYA	USPAT;	2003/06/02 07:50
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	2001/04/22 20 08
-	2	jp-10312060-\$.did.	USPAT;	2001/04/23 09:08
			US-PGPUB; EPO; JPO;	
		- ^ C T	DERWENT	
	2	jp-11109632-\$.did.	USPAT;	2001/04/23 09:16
-		Jp-11103032-3.d1d.	US-PGPUB;	2001,01,23 03.10
		jp-11109632-\$.did. EAST SEARCH	EPO; JPO;	
	İ	STARCI	DERWENT	
_	2	jp-09073173-\$.did.	USPAT;	2001/04/23 09:20
	1		US-PGPUB;	
}	1		EPO; JPO;	
	•	\ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \	DERWENT	
-	2	jp-10003169-\$.did.	USPAT;	2001/04/23 14:09
Ì		1)0 '	US-PGPUB;	
		jp-10003169-\$.did. DO NOT jp-08012626-\$.did. RemovE	EPO; JPO;	
		OWOLD	DERWENT	
-	2	jp-08012626-\$.did. ( 2 )	USPAT;	2001/04/23 09:29
		•	US-PGPUB;	
	-		EPO; JPO;	
	2	in 10002076 ¢ did	DERWENT USPAT:	2001/04/23 09:30
_		jp-10083076-\$.did.	US-PGPUB;	2001/04/23 09:30
			EPO; JPO;	
	i i		DERWENT	·
_	2	jp-07196743-\$.did.	USPAT;	2001/04/23 09:33
	_	Jp 0.130,13 4.41	US-PGPUB;	,,
			EPO; JPO;	
			DERWENT	.
-	0	jp-103169-\$.did.	USPAT;	2001/04/23 09:34
			US-PGPUB;	
			EPO; JPO;	·
			DERWENT	
-	2	jp-10003169-\$.did.	USPAT;	2001/04/23 09:37
			US-PGPUB;	1
			EPO; JPO;	
_		in-00002025-5 did	DERWENT USPAT;	2001/04/23 09:40
-	2	jp-08082925-\$.did.	US-PGPUB;	2001/04/23 09.40
	1		EPO; JPO;	
1	1		DERWENT	
-	2	jp-07234511-\$.did.	USPAT;	2001/04/23 09:47
	_		US-PGPUB;	
			EPO; JPO;	
]	1		DERWENT	
] -	2	ep-663616-\$.did.	USPAT;	2002/09/11 11:16
			US-PGPUB;	]′
			EPO; JPO;	
		(AVERTANCE OF AVAILABLE OF THE AVAILABLE	DERWENT	2002/05/20 17 42
-	4	1 '	USPAT;	2003/05/20 17:43
		(labile or cleavable or responsive or	US-PGPUB; EPO; JPO;	
		generat\$3))	DERWENT	
_	1	wo-9961956-\$.did.	USPAT;	2001/04/23 10:03
		, , , , , , , , , , , , , , , , , ,	US-PGPUB;	-5552, 51, 25 10.05
			EPO; JPO;	
			DERWENT	
-	1	1998JP-0227336.prai. or	USPAT;	2001/04/23 10:03
		1998JP-0143535.prai.	US-PGPUB;	
		_	EPO; JPO;	
[			DERWENT	

-	1	wo-9961404-\$.did.	USPAT;	2001/04/23 10:05
1			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	2	jp-2000019737-\$.did.	USPAT;	2001/04/23 10:06
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	2	jp-11327148-\$.did.	USPAT;	2001/04/23 10:07
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	2	jp-10221852-\$.did.	USPAT;	2001/04/23 10:10
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	2	jp-10115925-\$.did.	USPAT;	2001/04/23 10:13
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	l <i></i>
-	2	jp-09297401-\$.did.	USPAT;	2001/04/23 10:47
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	1	ep-326977-\$.did.	USPAT;	2001/04/23 10:48
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	0	ep292219-\$.did.	USPAT;	2001/04/23 10:48
			US-PGPUB;	
			EPO; JPO;	
	_		DERWENT	
-	2	ep-292219-\$.did.	USPAT;	2001/04/23 10:50
			US-PGPUB;	
			EPO; JPO;	
Ì		(("5077544") ("5000771") ("4004244")	DERWENT	2001/04/22 10:52
-	9	(("6077644") or ("5929271") or ("4994344")	USPAT;	2001/04/23 10:53
		or ("4666821")).PN.	US-PGPUB;	
			EPO; JPO; DERWENT	
	1	(NAKANO-T NAKANO-TATSUYA) and adamant\$4	USPAT;	2003/05/20 17:43
-	24	(NANANO-I NANANO-IAISUIA) and adamant94	US-PGPUB;	2003/03/20 17:43
			EPO; JPO;	
			DERWENT	
_	9986	(acid adj (labile or cleavable or responsive	USPAT;	2001/04/23 11:08
1	7,00	or generat\$3))	US-PGPUB;	2501/04/25 11.00
		or acustachall	EPO; JPO;	
			DERWENT	
_	2056	((acid adj (labile or cleavable or	USPAT;	2001/04/23 11:09
	2030	responsive or generat\$3))) and (resin or	US-PGPUB;	====, ==, ==, ===
		binder) and \$5resist	EPO; JPO;	
			DERWENT	
-	869	(((acid adj (labile or cleavable or	USPAT;	2001/04/23 11:09
		responsive or generat\$3))) and (resin or	US-PGPUB;	
	1	binder) and \$5resist) and 430/\$.ccls.	EPO; JPO;	
			DERWENT	
-	268	((((acid adj (labile or cleavable or	USPAT;	2001/04/23 11:09
		responsive or generat\$3))) and (resin or	US-PGPUB;	
		binder) and \$5resist) and 430/\$.ccls.) and	EPO; JPO;	
		(monocyclic or polycyclic or alicyclic)	DERWENT	
	1	1		

-	268	<pre>(((((acid adj (labile or cleavable or responsive or generat\$3))) and (resin or</pre>	USPAT; US-PGPUB;	2001/04/23 11:08
		binder) and \$5resist) and 430/\$.ccls.) and	EPO; JPO;	
		(monocyclic or polycyclic or alicyclic)) not	DERWENT	
		((NAKANO-T NAKANO-TATSUYA) or		
		jp-10312060-\$.did. or jp-11109632-\$.did. or		
		jp-09073173-\$.did. or jp-10003169-\$.did. or   jp-08012626-\$.did. or jp-10083076-\$.did. or		
	]	jp-07196743-\$.did. or jp-103169-\$.did. or		
		jp-10003169-\$.did. or jp-08082925-\$.did. or		
		jp-07234511-\$.did. or ep-663616-\$.did. or		
		((NAKANO-T NAKANO-TATSUYA) and (acid adj		
		(labile or cleavable or responsive or qenerat\$3))) or wo-9961956-\$.did. or		
		(1998JP-0227336.prai. or		
		1998JP-0143535.prai.) or wo-9961404-\$.did.		
		or jp-2000019737-\$.did. or		
		jp-11327148-\$.did. or jp-10221852-\$.did. or   jp-10115925-\$.did. or jp-09297401-\$.did. or		
		ep-326977-\$.did. or ep292219-\$.did. or		
		ep-292219-\$.did.)		
-	241	(((((acid adj (labile or cleavable or	USPAT;	2001/04/23 11:09
		responsive or generat\$3))) and (resin or binder) and \$5resist) and 430/\$.ccls.) and	US-PGPUB; EPO; JPO;	
İ		(monocyclic or polycyclic or alicyclic)) not	DERWENT	
<b>i</b>		((NAKANO-T NAKANO-TATSUYA) or	· = · · · <del>-</del>	
		jp-10312060-\$.did. or jp-11109632-\$.did. or		
		jp-09073173-\$.did. or jp-10003169-\$.did. or		
		jp-08012626-\$.did. or jp-10083076-\$.did. or jp-07196743-\$.did. or jp-103169-\$.did. or		
		jp-10003169-\$.did. or jp-08082925-\$.did. or		
		jp-07234511-\$.did. or ep-663616-\$.did. or		
		((NAKANO-T NAKANO-TATSUYA) and (acid adj		
		(labile or cleavable or responsive or qenerat\$3))) or wo-9961956-\$.did. or		
		(1998JP-0227336.prai. or		
		1998JP-0143535.prai.) or wo-9961404-\$.did.		
		or jp-2000019737-\$.did. or		
İ		jp-11327148-\$.did. or jp-10221852-\$.did. or   jp-10115925-\$.did. or jp-09297401-\$.did. or		
		ep-326977-\$.did. or ep292219-\$.did. or		
		ep-292219-\$.did.)) and (acid near generat\$3)		
-	3087	1	USPAT;	2001/04/23 11:09
		responsive))	US-PGPUB;	
			EPO; JPO; DERWENT	
_	522	((acid adj (labile or cleavable or	USPAT;	2001/04/23 11:09
		responsive))) and (resin or binder) and	US-PGPUB;	
		\$5resist	EPO; JPO;	
_	133	(((acid adj (labile or cleavable or	DERWENT USPAT;	2001/04/23 11:09
	133	responsive))) and (resin or binder) and	US-PGPUB;	2001,01,23 11.09
		\$5resist) and (monocyclic or polycyclic or	EPO; JPO;	
1		alicyclic)	DERWENT	2002/04/15 15 55
<del>-</del>	105	((((acid adj (labile or cleavable or responsive))) and (resin or binder) and	USPAT; US-PGPUB;	2002/04/15 15:35
		\$5resist) and (monocyclic or polycyclic or	EPO; JPO;	
		alicyclic)) and 430/\$.ccls.	DERWENT	
-	78	((((acid adj (labile or cleavable or	USPAT;	2001/11/06 08:21
		responsive))) and (resin or binder) and	US-PGPUB;	
		\$5resist) and (monocyclic or polycyclic or alicyclic)) and 430/\$.ccls.) and (acid near	EPO; JPO; DERWENT	·
		generat\$3)	-2	
-	36	(CLARKE-YVETTE CLARKE-YVETTE-M) and (resist	USPAT;	2001/11/06 08:21
		or photoresist)	US-PGPUB;	
			EPO; JPO; DERWENT	
_	61	CLARKE-YVETTE CLARKE-YVETTE-M	USPAT;	2001/04/23 11:27
			US-PGPUB;	====, ==, ==, ==
			EPO; JPO;	
			DERWENT	<u> </u>

			TIODAM	2001/04/22 12:10
-	2	("5968713").PN.	USPAT; US-PGPUB; EPO; JPO;	2001/04/23 13:10
			DERWENT	
-	19	pinanone	USPAT; US-PGPUB;	2001/04/23 13:10
			EPO; JPO;	
_	1	("6218569").PN.	DERWENT USPAT;	2001/04/23 14:04
			US-PGPUB; EPO; JPO;	
			DERWENT	
-	119	(((((acid adj (labile or cleavable or	USPAT;	2001/11/06 08:23
		responsive))) and (resin or binder) and \$5resist) and (monocyclic or polycyclic or	US-PGPUB; EPO; JPO;	
		alicyclic)) and 430/\$.ccls.) and (acid near generat\$3)	DERWENT	
-	58	(CLARKE-YVETTE CLARKE-YVETTE-M) and (resist	USPAT;	2001/11/06 08:22
		or photoresist)	US-PGPUB; EPO; JPO;	
			DERWENT	
-	30	(NAKANO-T NAKANO-TATSUYA) and adamant\$4	USPAT;	2003/05/20 17:43
			US-PGPUB; EPO; JPO;	
			DERWENT	
-	206	((((((acid adj (labile or cleavable or	USPAT;	2001/11/06 08:23
		responsive))) and (resin or binder) and	US-PGPUB;	
		\$5resist) and (monocyclic or polycyclic or alicyclic)) and 430/\$.ccls.) and (acid near	EPO; JPO; DERWENT	
		generat\$3)) ((CLARKE-YVETTE CLARKE-YVETTE-M)	DERWENT	
		and (resist or photoresist)) ((NAKANO-T		
	57	NAKANO-TATSUYA) and adamant\$4) ((((((acid adj (labile or cleavable or	USPAT;	2002/04/15 15:36
-	3/	responsive))) and (resin or binder) and	US-PGPUB;	2002/04/13 13.30
•		\$5resist) and (monocyclic or polycyclic or	EPO; JPO;	
		alicyclic)) and 430/\$.ccls.) and (acid near	DERWENT	
		generat\$3)) ((CLARKE-YVETTE CLARKE-YVETTE-M) and (resist or photoresist)) ((NAKANO-T		
		NAKANO-TATSUYA) and adamant\$4)) and		
	140	@pd>=20010331	HCDATT.	2002/04/15 15:36
_	149	<pre>(((((((acid adj (labile or cleavable or responsive))) and (resin or binder) and</pre>	USPAT; US-PGPUB;	2002/04/15 15:36
		\$5resist) and (monocyclic or polycyclic or	EPO; JPO;	
		alicyclic)) and 430/\$.ccls.) and (acid near	DERWENT	
		generat\$3)) ((CLARKE-YVETTE CLARKE-YVETTE-M)		
		and (resist or photoresist)) ((NAKANO-T NAKANO-TATSUYA) and adamant\$4)) not		
		(((((((acid adj (labile or cleavable or	•	
		responsive))) and (resin or binder) and		
		\$5resist) and (monocyclic or polycyclic or alicyclic)) and 430/\$.ccls.) and (acid near		
	,	generat\$3)) ((CLARKE-YVETTE CLARKE-YVETTE-M)		
		and (resist or photoresist)) ((NAKANO-T		
		NAKANO-TATSUYA) and adamant\$4)) and		
_	254	@pd>=20010331)   (adamant\$4 anthrac\$4 tricyclodecan\$5) adj	USPAT;	2001/11/06 10:15
		methacrylate	US-PGPUB;	,,
			EPO; JPO;	
			DERWENT	

-	250	((adamant\$4 anthrac\$4 tricyclodecan\$5) adj	USPAT;	2001/11/06 10:15
		methacrylate) not ((((((acid adj (labile	US-PGPUB;	
!		or cleavable or responsive))) and (resin or	EPO; JPO;	
		binder) and \$5resist) and (monocyclic or	DERWENT	
		polycyclic or alicyclic)) and 430/\$.ccls.)		
		and (acid near generat\$3)) ((CLARKE-YVETTE		
		CLARKE-YVETTE-M) and (resist or		
		photoresist)) ((NAKANO-T NAKANO-TATSUYA) and		,
		adamant\$4)) not (((((((acid adj (labile or		
		cleavable or responsive))) and (resin or binder) and \$5resist) and (monocyclic or		
		polycyclic or alicyclic)) and 430/\$.ccls.)		
		and (acid near generat\$3)) ((CLARKE-YVETTE		
		CLARKE-YVETTE-M) and (resist or		
Ì		photoresist)) ((NAKANO-T NAKANO-TATSUYA) and		
		adamant\$4)) and @pd>=20010331))		
_	248		USPAT;	2001/11/06 10:15
		methacrylate) not ((((((acid adj (labile	US-PGPUB;	, ,
		or cleavable or responsive))) and (resin or	EPO; JPO;	
		binder) and \$5resist) and (monocyclic or	DERWENT	
		polycyclic or alicyclic)) and 430/\$.ccls.)		
		and (acid near generat\$3)) ((CLARKE-YVETTE		
		CLARKE-YVETTE-M) and (resist or		
		photoresist)) ((NAKANO-T NAKANO-TATSUYA) and		
		adamant\$4)) and @pd>=20010331)		
-	4	(NAKANO-T NAKANO-TATSUYA) and (acid adj	USPAT;	2002/04/15 15:36
		(labile or cleavable or responsive or	US-PGPUB;	
		generat\$3))	EPO; JPO;	
		(	DERWENT	2002/04/15 15 26
-	34	(NAKANO-T NAKANO-TATSUYA) and adamant\$4	USPAT;	2002/04/15 15:36
			US-PGPUB; EPO; JPO;	
ļ			DERWENT	
	177	((((acid adj (labile or cleavable or	USPAT;	2002/04/15 15:37
-	1//	responsive))) and (resin or binder) and	US-PGPUB;	2002/04/13 13.37
		\$5resist) and (monocyclic or polycyclic or	EPO; JPO;	
		alicyclic)) and 430/\$.ccls.	DERWENT	
_	107	((((((acid adj (labile or cleavable or	USPAT;	2002/04/15 15:37
	••	responsive))) and (resin or binder) and	US-PGPUB;	, - ,
		\$5resist) and (monocyclic or polycyclic or	EPO; JPO;	
	1	alicyclic)) and 430/\$.ccls.) and (acid near	DERWENT	
		generat\$3)) ((CLARKE-YVETTE CLARKE-YVETTE-M)		
		and (resist or photoresist)) ((NAKANO-T		
		NAKANO-TATSUYA) and adamant\$4)) and	1	
		@pd>=20010331		
-	58	isobornyl same polycyclic	USPAT;	2002/04/15 15:56
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	12	((spiro adj ring) (terpene adj ring)	USPAT;	2002/04/15 16:01
		(steroid adj bile adj acid) (digitaloid adj	US-PGPUB;	
		ring) (camphor adj ring) (triterpene adj	EPO; JPO;	
		ring)) same (tricyclic tetracyclic (ring adj	DERWENT	
		assembly))	l	

-	29	(("2002034704") or ("2002031720") or	USPAT;	2002/04/16 10:28
Ì		("2002031719") or ("6348297") or	US-PGPUB	
1		("2002015913") or ("2002009668") or		
		("2002009667") or ("2002009666") or		
		("2002007031") or ("2002006582") or		
:		("2002004569") or ("2002004178") or		
		("2001051316") or ("2001051315") or		
		("2001049075") or ("2001046641") or		
		("2001044072") or ("2001044071") or		
		("2001044070") or ("2001038971") or		
:		("2001036593") or ("2001035394") or		
		("2001033994") or ("2001033990") or		
		("2001033987") or ("6306554") or		
		("2001031421") or ("6303266") or		
		("2001026901") or ("2001024763") or		:
		("6294309") or ("2001023050") or		
		("2001024763") or ("6294309") or		
	ĺ	("2001023050") or ("6291130") or ("6284429")		
	Ì	or ("6280911") or ("6280898") or ("6280897")		
		or ("2001016298") or ("2001014428") or		
		("6270941") or ("6265131") or ("6248920") or		
				·
		("2001003772") or ("2001003640") or		
		("6245485") or ("6239231") or ("6225476") or		
		("6207342") or ("6200725") or ("6156481") or		
		("6136501") or ("6087063") or ("6077644") or		
į i	ĺ	("6054254") or ("6042991") or ("6013416") or		
		("6010826") or ("6239231") or ("6280897") or		
		("5968713") or ("5929271") or ("5910392") or		
		("2002042016") or ("6348297") or ("6042991")		
		or ("6248920") or ("6329125") or		
]		("5910392")).PN.	•	
1_	1	("6245485").PN.	USPAT	2002/04/16 14:40
1 _	1	("6368227").PN.	USPAT	2002/04/16 14:46
-	_	("6280897").PN.	USPAT	2002/04/16 14:46
-	1		USPAT;	2002/04/10 14:40
-	2	us-20020115883-\$.did. us-20010014428-\$.did.	•	2002/03/11 11:03
	]		US-PGPUB;	·
			EPO; JPO;	
			DERWENT	
-	2	("6348297").PN.	USPAT;	2002/09/11 11:03
1			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
_	ا ه	("00001 2").PN.	USPAT;	2002/09/11 11:03
		, , , , , , , , , , , , , , , , , , ,	US-PGPUB;	, ., ==
			EPO; JPO;	
			DERWENT	
		/ 2002011E002 & 4:4 20010014420 & 4:4		2002/09/11 11:09
-	4	(us-20020115883-\$.did. us-20010014428-\$.did.	USPAT;	2002/03/11 11:09
		) (("6348297").PN.)	US-PGPUB;	
			EPO; JPO;	1
			DERWENT	
-	1	1999JP-0315264.prai. 1999JP-0092990.prai.	USPAT;	2002/09/11 11:10
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
_	7	(("5585507") or ("5691111") or ("5635332")	USPAT;	2002/09/11 11:10
	1	or ("5756850")).PN.	US-PGPUB;	
	1	01 ( 3/30030 // 1111.	EPO; JPO;	
			DERWENT	
	050	NAMANO T NAMANO-TATCITYA	USPAT;	2002/09/11 11:16
-	953	NAKANO-T NAKANO-TATSUYA	•	2002,05,11 11.10
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	8	(NAKANO-T NAKANO-TATSUYA) and (acid adj	USPAT;	2003/05/20 17:44
		(labile or cleavable or responsive or	US-PGPUB;	
	1	generat\$3))	EPO; JPO;	1
	1	<del>-</del>	DERWENT	
_	49	(NAKANO-T NAKANO-TATSUYA) and adamant\$4	USPAT;	2002/09/11 11:49
1		1	US-PGPUB;	1
			EPO; JPO;	
			DERWENT	
I	l		PERMENT	

-	44	((NAKANO-T NAKANO-TATSUYA) and adamant\$4 )	USPAT;	2003/05/20 17:43
	•	not(((NAKANO-T NAKANO-TATSUYA) and (acid adj	US-PGPUB;	i
		(labile or cleavable or responsive or	EPO; JPO;	1
	1	generat\$3)) ) ((("5585507") or ("5691111")	DERWENT	
		or ("5635332") or ("5756850")).PN.)		
		(1999JP-0315264.prai. 1999JP-0092990.prai.)		
		((us-20020115883-\$.did.		
		us-20010014428-\$.did. ) (("6348297").PN.)))		
_	44	((NAKANO-T NAKANO-TATSUYA) and adamant\$4 )	USPAT;	2002/09/11 12:40
		not (((NAKANO-T NAKANO-TATSUYA) and (acid	US-PGPUB;	' '
		adj (labile or cleavable or responsive or	EPO; JPO;	
		generat\$3)) ) ((("5585507") or ("5691111")	DERWENT	
		or ("5635332") or ("5756850")).PN.)		
		(1999JP-0315264.prai. 1999JP-0092990.prai.)		
		((us-20020115883-\$.did.		
		us-20010014428-\$.did. ) (("6348297").PN.)))		
_	2	jp-10143535-\$.did.	USPAT;	2002/09/11 12:40
	_	Jp 1011000 4.411	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
_	4	(("6004720") or ("6235851")).PN.	USPAT;	2002/09/11 12:58
	1		US-PGPUB;	
			EPO; JPO;	
	[		DERWENT	
_	1	("6245485").PN.	USPAT	2002/09/11 12:58
-	9	!	USPAT;	2003/05/20 17:43
		(labile or cleavable or responsive or	US-PGPUB;	,,
		generat\$3))	EPO; JPO;	
		· · · · · · · · · · · · · · · · · ·	DERWENT	
_	60	(NAKANO-T NAKANO-TATSUYA) and adamant\$4	USPAT;	2003/05/20 17:43
		(	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
_	60	(NAKANO-T NAKANO-TATSUYA) and adamant\$4	USPAT;	2003/05/20 17:43
		,	US-PGPUB;	, i
			EPO; JPO;	
			DERWENT	
_	9	(NAKANO-T NAKANO-TATSUYA) and (acid adj	USPAT;	2003/05/20 17:44
		(labile or cleavable or responsive or	US-PGPUB;	
		generat\$3))	EPO; JPO;	
			DERWENT	
-	63	((NAKANO-T NAKANO-TATSUYA) and (acid adj	USPAT;	2003/05/20 17:51
		(labile or cleavable or responsive or	US-PGPUB;	
	1	generat\$3)) ) ((NAKANO-T NAKANO-TATSUYA) and	EPO; JPO;	
•		adamant\$4 ) ((NAKANO-T NAKANO-TATSUYA) and	DERWENT	1
		adamant\$4 ) ((NAKANO-T NAKANO-TATSUYA) and		
		(acid adj (labile or cleavable or responsive		
		or generat\$3)) )		
-	0	1-hydroxy-3-1-acryloxyloxy-12-dimehtylpropyl	USPAT;	2003/05/20 17:52
		adj adamantine	US-PGPUB;	
		·	EPO; JPO;	
			DERWENT	/ /
-	0	1-hydroxy-3-1-acryloxyloxy-12-dimehtylpropylac		2003/05/20 17:52
			US-PGPUB;	
1			EPO; JPO;	
1			DERWENT	
-	0	1-hydroxy-3-1-acryloxyloxy-12-dimethylpropylac		2003/05/20 17:53
			US-PGPUB;	
	1		EPO; JPO;	
			DERWENT	
-	0	1-hydroxy-3-1-acryloxyloxy-12-dimethylpropyl	USPAT;	2003/05/20 17:53
		adj adamantine	US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	0	1-hydroxy-3-1-acryloxyloxy-12-dimethylpropyl	USPAT;	2003/05/20 17:53
	1	adj adamantane	US-PGPUB;	
			EPO; JPO;	
			DERWENT	2002/05/20 55 55
-	0	2-hydroxy-6-acryloyloxy-tricyclo\$5decane	USPAT;	2003/05/20 17:53
		•	US-PGPUB;	
	1		EPO; JPO;	
1			DERWENT	L

-	0	2-hydroxy6acryloyloxytricyclo\$5decane	USPAT;	2003/05/20 17:53
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
	о	2hydroxy6acryloyloxytricyclo\$5decane	USPAT;	2003/05/20 18:14
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	2	("6440636").PN.	USPAT;	2003/05/20 18:41
			US-PGPUB;	
			EPO; JPO;	
			DERWENT	
-	0	6440636.URPN.	USPAT	2003/05/20 18:26
-	2	("5968713"   "6303266").PN.	USPAT	2003/05/20 18:27
-	2	("6218569").PN.	USPAT;	2003/05/20 18:41
			US-PGPUB;	
			EPO; JPO;	ĺ
			DERWENT	
	0	6218569.URPN.	USPAT	2003/05/20 18:43
-	0	6218569.URPN.	USPAT	2003/05/20 18:43

PAT-NO:

JP02002116544A

DOCUMENT-IDENTIFIER: JP 2002116544 A

TITLE:

POSITIVE TYPE PHOTORESIST COMPOSITION

PUBN-DATE:

April 19, 2002

INVENTOR-INFORMATION:

NAME

COUNTRY

SATO, KENICHIRO

N/A

ASSIGNEE-INFORMATION:

NAME

COUNTRY

FUJI PHOTO FILM CO LTD

N/A

APPL-NO:

JP2000310761

APPL-DATE: October 11, 2000

INT-CL (IPC): G03F007/039, C08F232/00, C08K005/00,

C08L045/00 , G03F007/004

, H01L021/027

## ABSTRACT:

PROBLEM TO BE SOLVED: To provide a positive type photoresist composition

less liable to cause development defects in the production of a semiconductor

device, excellent in adhesion on an inorganic antireflection film and excellent

also in exposure margin (in particular, exposure margin in the case of isolated

lines), sensitivity change with age, etc.

SOLUTION: The positive type photoresist composition contains (A) a resin

containing repeating structural units with norbornene and repeating structural

units containing a specified alicyclic hydrocarbon structure

06/02/2003, EAST Version: 1.03.0007

and having a velocity of dissolution in an alkali developing solution increased by the action of an acid and (B) a compound which generates the acid when irradiated with active light or radiation.

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06/02/2003, EAST Version: 1.03.0007

 $\stackrel{\centerdot}{\rightarrow}$  ....Testing the current file.... screen

ENTER SCREEN EXPRESSION OR (END):end

=> screen 964 AND 970 AND 1015 AND 1051 AND 2067

L1 SCREEN CREATED

=>

Uploading C:\Program Files\Stnexp\Queries\09463059.str

L2 STRUCTURE UPLOADED

=> que L2 AND L1

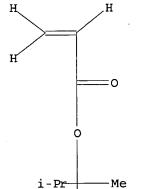
L3 QUE L2 AND L1

=> d

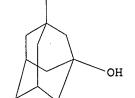
L3 HAS NO ANSWERS

L1 SCR 964 AND 970 AND 1015 AND 1051 AND 2067 L2 STR

L2 H H



compound ob



G1 Me,H

G2 H, Ak, Cy

G3 Cy,Ak

Structure attributes must be viewed using STN Express query preparation. L3 QUE ABB=ON PLU=ON L2 AND L1

=> s 13 sss sam

SAMPLE SEARCH INITIATED 07:44:46 FILE 'REGISTRY'
SAMPLE SCREEN SEARCH COMPLETED - 0 TO ITERATE

100.0% PROCESSED

0 ITERATIONS

0 ANSWERS

SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS: ONLINE \*\*COMPLETE\*\*

\*\*COMPLETE\*\* BATCH

PROJECTED ITERATIONS: PROJECTED ANSWERS:

O TO 0 0 TO

0

0 SEA SSS SAM L2 AND L1

=> FIL CAPLUS HCAPLUS USPATFULL USPAT2 COST IN U.S. DOLLARS .

SINCE FILE ENTRY

TOTAL SESSION

FULL ESTIMATED COST

0.40 0.61

FILE 'CAPLUS' ENTERED AT 07:44:52 ON 02 JUN 2003 USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT. PLEASE SEE "HELP USAGETERMS" FOR DETAILS. COPYRIGHT (C) 2003 AMERICAN CHEMICAL SOCIETY (ACS)

FILE 'HCAPLUS' ENTERED AT 07:44:52 ON 02 JUN 2003 USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT. PLEASE SEE "HELP USAGETERMS" FOR DETAILS. COPYRIGHT (C) 2003 AMERICAN CHEMICAL SOCIETY (ACS)

FILE 'USPATFULL' ENTERED AT 07:44:52 ON 02 JUN 2003 CA INDEXING COPYRIGHT (C) 2003 AMERICAN CHEMICAL SOCIETY (ACS)

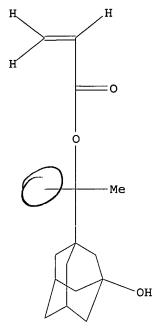
FILE 'USPAT2' ENTERED AT 07:44:52 ON 02 JUN 2003 CA INDEXING COPYRIGHT (C) 2003 AMERICAN CHEMICAL SOCIETY (ACS)

=> s 14

L5

0 L4

=> d L8 HAS NO ANSWERS L6 SCR 963 AND 970 AND 1015 AND 2067 L7 STR



Smot C

G1 Me,H G2 H,Ak,Cy G3 Cy,Ak

Structure attributes must be viewed using STN Express query preparation. L8 QUE ABB=ON PLU=ON L7 AND L6

=> s 18 sss sam SAMPLE SEARCH INITIATED 07:46:22 FILE 'REGISTRY' SAMPLE SCREEN SEARCH COMPLETED - 2 TO ITERATE

100.0% PROCESSED 2 ITERATIONS 2 ANSWERS

SEARCH TIME: 00.00,01

FULL FILE PROJECTIONS: ONLINE \*\*COMPLETE\*\*

BATCH \*\*COMPLETE\*\*

PROJECTED ITERATIONS: 2 TO 124

PROJECTED ANSWERS: 2 TO 124

L9 2 SEA SSS SAM L7 AND L6

=> d

L9 ANSWER 1 OF 2 REGISTRY COPYRIGHT 2003 ACS
RN 450410-08-9 REGISTRY
CN 2-Propenoic acid, 3,5-dihydroxytricyclo[3.3.1.13,7]dec-1-yl ester, polymer
with 1-(3-hydroxytricyclo[3.3.1.13,7]dec-1-yl)-1-methylethyl 2-propenoate
(9CI) (CA INDEX NAME)
MF (C16 H24 O3 . C13 H18 O4)x
CI PMS

PCT Polyacrylic

SR C

LC STN Files: CA, CAPLUS, USPATFULL

CM 1

CRN 262608-27-5 CMF C16 H24 O3

$$\begin{array}{c} \text{O} & \text{HO} \\ \text{H}_2\text{C} = \text{CH} - \text{C} - \text{O} \\ \text{Me} - \text{C} \end{array}$$

CM 2

CRN 216581-85-0 CMF C13 H18 O4

1 REFERENCES IN FILE CA (1957 TO DATE)

1 REFERENCES IN FILE CAPLUS (1957 TO DATE)

=> d 19 1-2

L9 ANSWER 1 OF 2 REGISTRY COPYRIGHT 2003 ACS

RN 450410-08-9 REGISTRY

CN 2-Propenoic acid, 3,5-dihydroxytricyclo[3.3.1.13,7]dec-1-yl ester, polymer with 1-(3-hydroxytricyclo[3.3.1.13,7]dec-1-yl)-1-methylethyl 2-propenoate (9CI) (CA INDEX NAME)

MF (C16 H24 O3 . C13 H18 O4)x

CI PMS

PCT Polyacrylic

SR CA

LC STN Files: CA, CAPLUS, USPATFULL

CM 1

CRN 262608-27-5 CMF C16 H24 O3

$$H_2C = CH - C - O$$
 $Me - C$ 
 $Me$ 

$$H_2C = CH - C - O$$
 $Me - C$ 
 $Me$ 

CM 2

CRN 216581-85-0 CMF C13 H18 O4

1 REFERENCES IN FILE CA (1957 TO DATE)
1 REFERENCES IN FILE CAPLUS (1957 TO DATE)

L9 ANSWER 2 OF 2 REGISTRY COPYRIGHT 2003 ACS

RN 412015-88-4 REGISTRY

CN 2-Propenoic acid, 1-(3-hydroxytricyclo[3.3.1.13,7]dec-1-yl)-1-methylethyl ester, polymer with 2,5-furandione, 1,2,3,4,4a,5,8,8a-octahydro-1,4:5,8-dimethanonaphthalene and tetrahydro-2-oxo-3-furanyl 2-propenoate (9CI) (CA INDEX NAME)

MF (C16 H24 O3 . C12 H16 . C7 H8 O4 . C4 H2 O3)x

CI PMS

PCT Polyacrylic, Polyester, Polyester formed, Polyother, Polyvinyl

SR CA

LC STN Files: CA, CAPLUS

CM 1

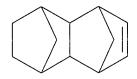
CRN 328249-37-2 CMF C7 H8 O4

CM 2

CRN 262608-27-5 CMF C16 H24 O3

CM 3

CRN 21635-90-5 CMF C12 H16



CM 4

CRN 108-31-6 CMF C4 H2 O3



- 1 REFERENCES IN FILE CA (1957 TO DATE)
- 1 REFERENCES IN FILE CAPLUS (1957 TO DATE)

=> FIL CAPLUS HCAPLUS USPATFULL USPAT2 COST IN U.S. DOLLARS

SINCE FILE ENTRY TOTAL SESSION

FULL ESTIMATED COST

5.44

11.26

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FILE 'USPAT2' ENTERED AT 07:46:44 ON 02 JUN 2003 CA INDEXING COPYRIGHT (C) 2003 AMERICAN CHEMICAL SOCIETY (ACS)

=> d his

(FILE 'HOME' ENTERED AT 07:44:07 ON 02 JUN 2003)

```
FILE 'REGISTRY' ENTERED AT 07:44:17 ON 02 JUN 2003
               SCREEN 964 AND 970 AND 1015 AND 1051 AND 2067
ь1
               STRUCTURE UPLOADED
L2
L3
               OUE L2 AND L1
             0 S L3 SSS SAM
L4
     FILE 'CAPLUS, HCAPLUS, USPATFULL, USPAT2' ENTERED AT 07:44:52 ON 02 JUN
     2003
             0 S L4
L_5
     FILE 'REGISTRY' ENTERED AT 07:45:52 ON 02 JUN 2003
               SCREEN 963 AND 970 AND 1015 AND 2067
L6
               STRUCTURE UPLOADED
L7
               QUE L7 AND L6
L8
             2 S L8 SSS SAM
L9
     FILE 'CAPLUS, HCAPLUS, USPATFULL, USPAT2' ENTERED AT 07:46:44 ON 02 JUN
     2003
=> s 19
L10
            5 L9
=> duplicates remove 110
DUPLICATE PREFERENCE IS 'CAPLUS, HCAPLUS, USPATFULL'
KEEP DUPLICATES FROM MORE THAN ONE FILE? Y/(N):n
PROCESSING COMPLETED FOR L10
             2 DUPLICATE REMOVE L10 (3 DUPLICATES REMOVED)
L11
=> d l11 1-2 ibib hitstr abs
L11 ANSWER 1 OF 2 CAPLUS COPYRIGHT 2003 ACS
                                                    DUPLICATE 1
                   2002:654986 CAPLUS
ACCESSION NUMBER:
                        137:192769
DOCUMENT NUMBER:
                        Polymeric compound and resin composition for
TITLE:
                        photoresist
                        Ushirogouchi, Toru; Okino, Takeshi; Asakawa, Koji;
INVENTOR(S):
                        Shida, Naomi; Funaki, Yoshinori; Tsutsumi, Kiyoharu;
                        Takaragi, Akira; Inoue, Keizo
                        Kabushiki Kaisha Toshiba, Japan; Daicel Chemical
PATENT ASSIGNEE(S):
                        Industries, Ltd.
                        U.S., 24 pp.
SOURCE:
                        CODEN: USXXAM
DOCUMENT TYPE:
                        Patent
LANGUAGE:
                        English
FAMILY ACC. NUM. COUNT:
PATENT INFORMATION:
                                                                    11-02-00
                    KIND DATE
                                         APPLICATION NO. DATE
     PATENT NO.
     ______
                                         -----
                     B1 20020827
                                        US 2000-703677
     US 6440636
                                                          20001102
                                     US 2000-703677
                                                          20001102
PRIORITY APPLN. INFO.:
IT
     450410-08-9P
     RL: PRP (Properties); SPN (Synthetic preparation); TEM (Technical or
     engineered material use); PREP (Preparation); USES (Uses)
        (polymeric compd. and resin compn. for photoresist)
RN
     450410-08-9 CAPLUS
     2-Propenoic acid, 3,5-dihydroxytricyclo[3.3.1.13,7]dec-1-yl ester, polymer
     with 1-(3-hydroxytricyclo[3.3.1.13,7]dec-1-yl)-1-methylethyl 2-propenoate
     (9CI) (CA INDEX NAME)
     CM
          1
     CRN 262608-27-5
```

CMF C16 H24 O3

CM 2

CRN 216581-85-0 CMF C13 H18 O4

GΙ

AB A polymeric compd. includes at least one monomeric unit of I (R1 = H, Me group; R2,3 = H, hydroxyl group). The polymeric compd. may include the monomeric unit and at least one monomeric unit selected from monomeric units represented by II, III (R1 = H, Me group; R4,5 = H, hydroxy, oxo, carboxyl group; R4,5 are not concurrently hydrogen atoms; R7,8 = H, hydroxyl, oxo group). The polymeric compd. have a high etching resistance in addn. to satisfactory transparency, alkali-soly., and adhesion.

REFERENCE COUNT: 13 THERE ARE 13 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L11 ANSWER 2 OF 2 CAPLUS COPYRIGHT 2003 ACS DUPLICATE 2

ACCESSION NUMBER: 2002:292089 CAPLUS

DOCUMENT NUMBER: 136:316934

TITLE: Positive-working photoresist composition for

fabrication of semiconductor device

INVENTOR(S): Sato, Kenichiro

PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan SOURCE: Jpn. Kokai Tokkyo Koho, 51 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent LANGUAGE: Japanese

PATENT INFORMATION:

PATENT NO. KIND DATE APPLICATION NO. DATE

10/11/00 --**---**-20001011 JP 2002116544 A2 20020419 JP 2000-310761 20001011 JP 2000-310761 PRIORITY APPLN. INFO.:

MARPAT 136:316934 OTHER SOURCE(S):

412015-88-4 IT

RL: TEM (Technical or engineered material use); USES (Uses) (pos.-working photoresist compn. for fabrication of semiconductor device)

412015-88-4 CAPLUS RN

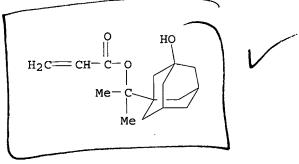
2-Propenoic acid, 1-(3-hydroxytricyclo[3.3.1.13,7]dec-1-yl)-1-methylethyl CN ester, polymer with 2,5-furandione, 1,2,3,4,4a,5,8,8a-octahydro-1,4:5,8dimethanonaphthalene and tetrahydro-2-oxo-3-furanyl 2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 328249-37-2 CMF C7 H8 O4

CM2

CRN 262608-27-5 CMF C16 H24 O3



CM 3 .

21635-90-5 CRN CMF C12 H16

GI

$$R_{n1}$$
 $R_{n2}$ 
 $R_{n3}$ 

Ι

The photoresist compn. contains a resin whose soly. rate in alk. developer increases by reaction with an acid and having a norbornene-based repeating unit I (a = 0, 1) and a OH group-contg. alicyclic hydrocarbyl ester group, and a compd. generating an acid upon irradn. with an actinic ray or radiation. The photoresist provides little fault pattern having improved adhesion to an inorg. antireflection film.